

Supplemental information:

A Novel Microwave ECR Plasma System for Damage-Free PEALD

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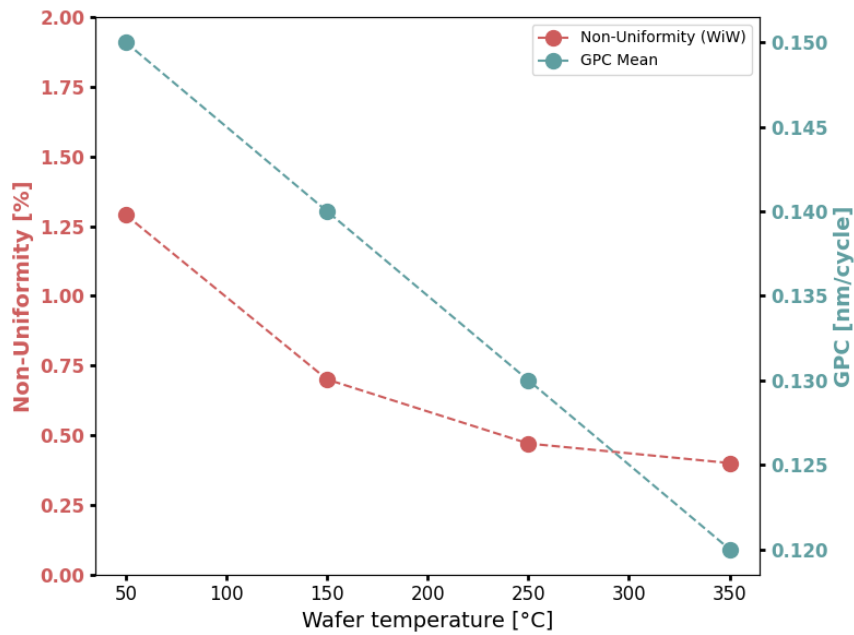


Figure 1 Al_2O_3 process: Non-Uniformity and growth per cycle as function of substrate temperature.

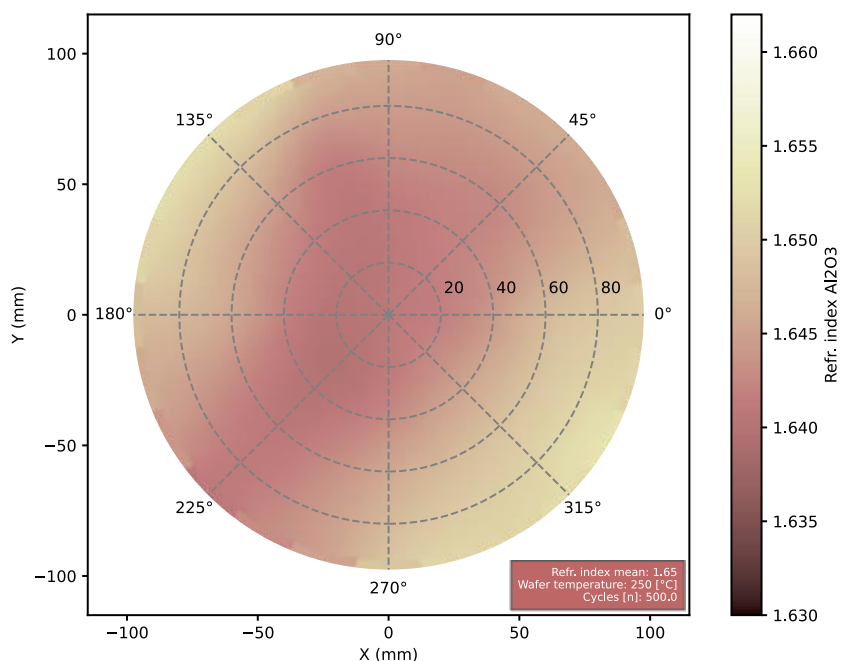


Figure 2 Refractive index of Al_2O_3 200mm wafer.